Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S1	168	427/248.1.ccls. and (mask shield shadow) and angle	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/04/19 15:54
S2	22	427/248.1.ccls. and (mask shield shadow) and angle and oblique	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/04/19 15:45
<b>S3</b>	11	(pelhos klemmer seigler).in. and oblique	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/04/19 15:47
S4	40	427/248.1.ccls. and (mask shield shadow) with angle	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/04/19 15:57
<b>S5</b>	20	427/2\$.ccls. and (mask shield shadow) with angle with oblique	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/04/19 15:59
S6	29	427/2\$.ccls. and (mask shield shadow) and angle with oblique and rotate	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/04/19 16:05
S7	4	427/2\$.ccls. and (mask shield shadow) and nozzle with (askew diagonal aslant asymmetrical angled oblique) and rotate	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/04/19 16:07
S8	17	427/2\$.ccls. and (mask shield shadow) and vapor\$5 with (askew diagonal aslant asymmetrical angled oblique) and rotate	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON ·	2005/04/19 16:09
S9	52	427/2\$.ccls. and (mask shield shadow) and vapor\$5 with (askew diagonal aslant asymmetrical angled oblique)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/04/19 16:14
S10	1	disc and (mask shield shadow) with vapor\$5 with (circumferential azimuthal radial) adj pattern	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/04/19 16:16
S11	1	substrate and (mask shield shadow) with vapor\$5 with (circumferential azimuthal radial) adj pattern	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/04/19 16:16
S12	4	substrate and (mask shield shadow) with vapor\$5 and (circumferential azimuthal radial) adj pattern	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/04/19 16:35

S13   2   Substrate with vapor\$5 with (circumferential azimuthal radial) adj pattern   S14   S18   S	_							
S15   31   118/720,721.ccls. and (disc disk wafer) with (pattern)   US-PCPUB; USPAT; EPO; JPO; DERWENT   US-PCPUB; USPAT; EPO; JPO; DERWENT   US-PCPUB; USPAT; EPO; JPO; DERWENT   USPAT; EPO; JPO; JPO; JPO; JPO; JPO; JPO; JPO; J	•	S13	2	(circumferential azimuthal radial)	USPAT; EPO; JPO;	OR	ON	2005/04/19 16:24
S15   31   118/720,721.ccls. and (disc disk wafer) with (pattern)   US-PGPUB; USPAT; EPO; JPO; DERWENT   US-PGPUB; USPAT; EPO; JPO; DERWENT   USP-GPUB; USPAT; EPO; JPO; DERWENT   USPAT;		S14	29	118/720,721.ccls. and oblique		OR	ON	2005/04/19 16:27
Wafer) with (pattern)					EPO; JPO;			
S17    0   118/720,721.cds. and 118/730.cds. and radial adj pattern   US-PGPUB; USPAT; EPO; JPO; DERWENT   US-PGPUB; US-PGPUB		S15	31		USPAT; EPO; JPO;	OR	ON	2005/04/19 16:30
S17		S16	90	118/720,721 ccls. and 118/730 ccls.		OR	ON	2005/04/19 16:32
S18					EPO; JPO;			
S19   26   (disc disk wafer) and (mask shield shadow) with vapor\$5 with (circumferential azimuthal radial)   US-PGPUB; EPO; JPO; DERWENT   US-PGPUB; USPAT; EPO; JPO; DERWENT   US-PGPUB; EPO; JPO; DERWENT   US-PGPU		S17	0		USPAT; EPO; JPO;	OR	ON	2005/04/19 16:32
S19   26   (disc disk wafer) and (mask shield shadow) with vapor\$5 with (circumferential azimuthal radial)   US-PGPUB; USPAT; EPO; JPO; DERWENT   US-PGPUB; OR ON   2005/04/20 10:56   USPAT; EPO; JPO; DERWENT   US-PGPUB; OR ON   2005/04/20 10:56   USPAT; EPO; JPO; DERWENT   US-PGPUB; OR ON   2005/04/20 10:56   USPAT; EPO; JPO; DERWENT   US-PGPUB; OR ON   2005/04/19 17:00   US-PGPUB; OR ON   2005/04/19 17:00   US-PGPUB; OR ON   2005/04/19 17:00   US-PGPUB; OR OR OFF   2005/04/20 08:56   US-PGPUB; OR OR OFF   2005/04/20 08:56   US-PGPUB; OR		S18	13			OR	ON	2005/04/19 16:32
Shadow) with vapor\$5 with (circumferential azimuthal radial)					EPO; JPO;			
Shadow) with vapor\$5 with control\$4 near3 pattern		S19	26	shadow) with vapor\$5 with	USPAT; EPO; JPO;	OR	ON	2005/04/19 16:55
Shadow) with vapor\$5 with control\$4 with pattern		<b>S21</b>	<b>2</b>	shadow) with vapor\$5 with	USPAT; EPO; JPO;	OR	ON	2005/04/20 10:56
S25 534 (disc disk wafer) and (mask shield shadow) with vapor\$5 with pattern S26 1 (disc disk wafer) and (mask shield shadow) with vapor\$5 with pattern S26 2005/04/20 10:56 US-PGPUB; US-PGPUB; OR US-PGPUB; US-PGP		S22	13	shadow) with vapor\$5 with	USPAT; EPO; JPO;	OR	ON	2005/04/19 17:00
S25 534 (disc disk wafer) and (mask shield shadow) with vapor\$5 with pattern  S26 1 (disc disk wafer) and (mask shield shadow) with vapor\$5 with pattern with radial  S27		S23	6		la cere la la companya de la companya del companya del companya de la companya de	OR	OFF	2005/04/20 08:56
S25   534   (disc disk wafer) and (mask shield shadow) with vapor\$5 with pattern   US-PGPUB; USPAT; EPO; JPO; DERWENT   US-PGPUB; OR   ON   2005/04/20 10:56   US-PGPUB; OR   ON   2005/04/20 10:56   US-PGPUB; OR   ON   2005/04/20 10:56   US-PGPUB; USPAT; EPO; JPO;   USPAT; EPO; JPO;   ON   DERWENT   USPAT; EPO; JPO;   OR   ON   2005/04/20 10:56   USPAT; EPO; JPO;   OR   ON   DERWENT   USPAT;   OR   ON   DERWENT   OR   ON   O			Professional Company	( 2003001A/42 )).KM				
shadow) with vapor\$5 with pattern  S26  USPAT; EPO; JPO; DERWENT  US-PGPUB; Shadow) with vapor\$5 with pattern WS-PGPUB; Shadow) with vapor\$5 with pattern WISPAT; EPO; JPO; WISPAT; EPO; JPO; WISPAT; EPO; JPO;					DERWENT			
shadow) with vapor\$5 with pattern USPAT; with radial EPO; JPO;		S25	534		USPAT; EPO; JPO;	OR	ON	2005/04/20 10:56
with radial EPO; JPO;		S26	1		The second of th	OR	ON	2005/04/20 10:56
					EPO; JPO;			